

GPD Finland 2017 Workshop  
“Advances in Coatings for Glass and Plastics”  
June 28, 2017, Tampere

“Flexible organic electronics & R2R coating technologies  
in Fraunhofer FEP”

Koichi Suzuki

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# Content

1. Background

2. R2R coating technologies

1) Key component technologies

2) Coatings on flexible ultra thin glass

3. Flexible OLED lighting

4. Summary

# Background of my activities

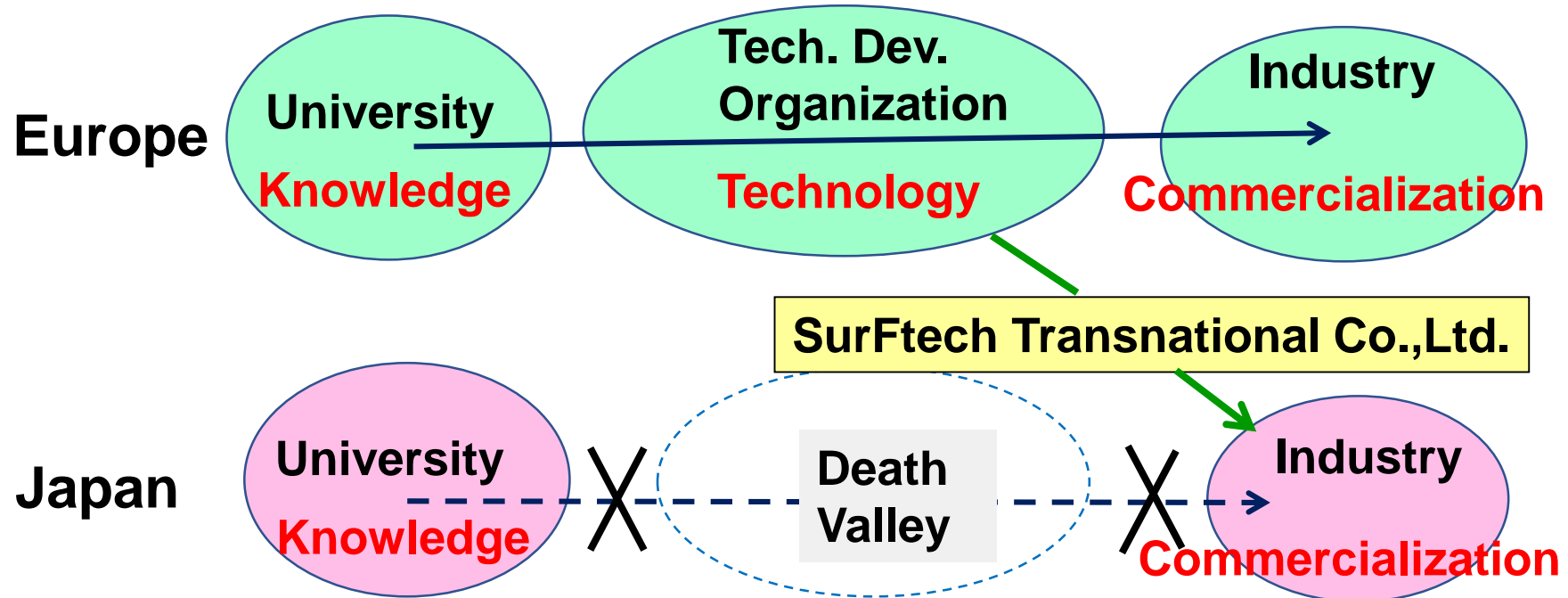
1992~1996: Technical advisor in Belgium glass company

**Contacts with various European institutes through ICCG**

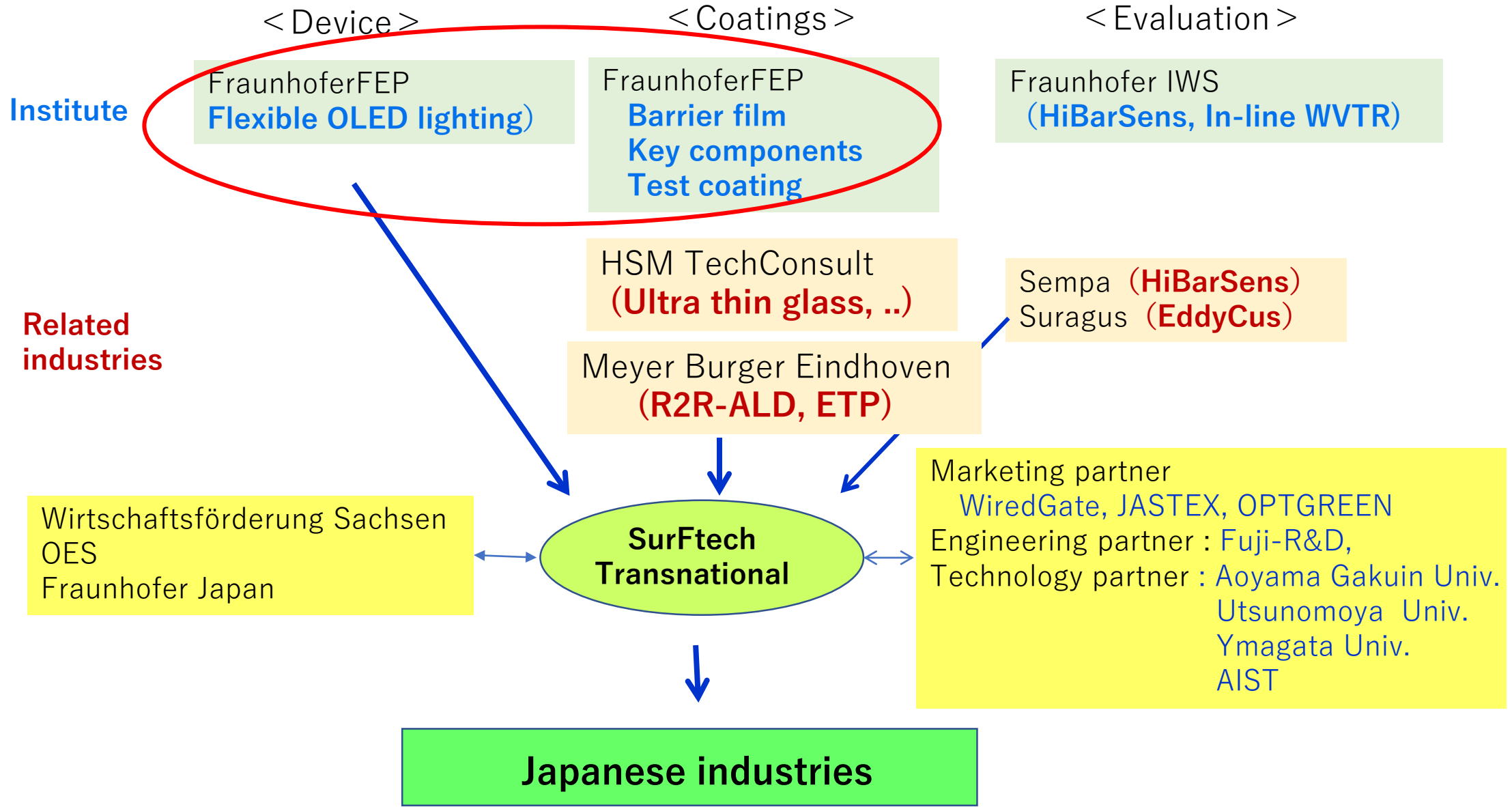
1998~Now: Technology transfer business as SurFtech Transnational Co.,Ltd

Germany: **Fraunhofer, INM**

The Netherlands: **TNO**



# Coordination of EU-Japan Collaboration for Organic Electronics



# Fraunhofer FEP

for Organic Electronics, electron beam, plasma technology

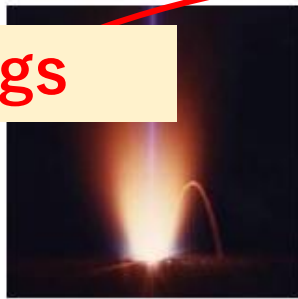
Foundation: 1991  
Staffs : 216

- \* World top level in vacuum coating
- \* Development for 2 years ahead
- \* **Technology package with hardware**
- \* OLED



■ Core competences:

Coatings



ELECTRON BEAM  
TECHNOLOGY



SPUTTERING  
TECHNOLOGY



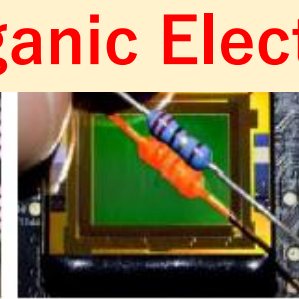
PLASMA-  
ACTIVATED HIGH-  
RATE DEPOSITION



HIGH-RATE  
PECVD



TECHNOLOGIES  
FOR ORGANIC  
ELECTRONICS



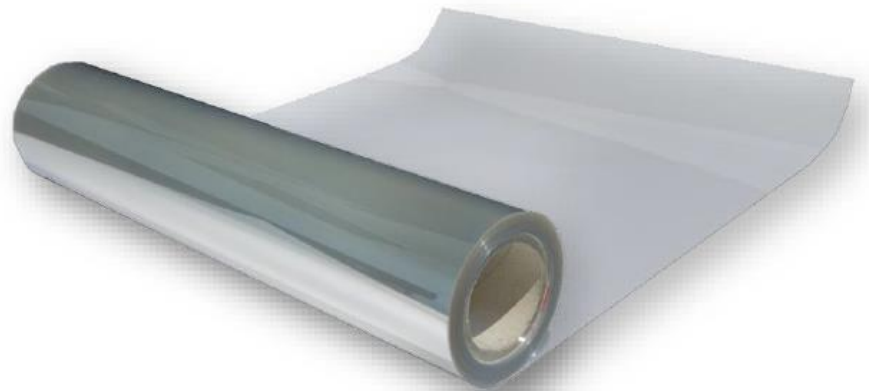
IC AND SYSTEM  
DESIGN

Organic Electronics

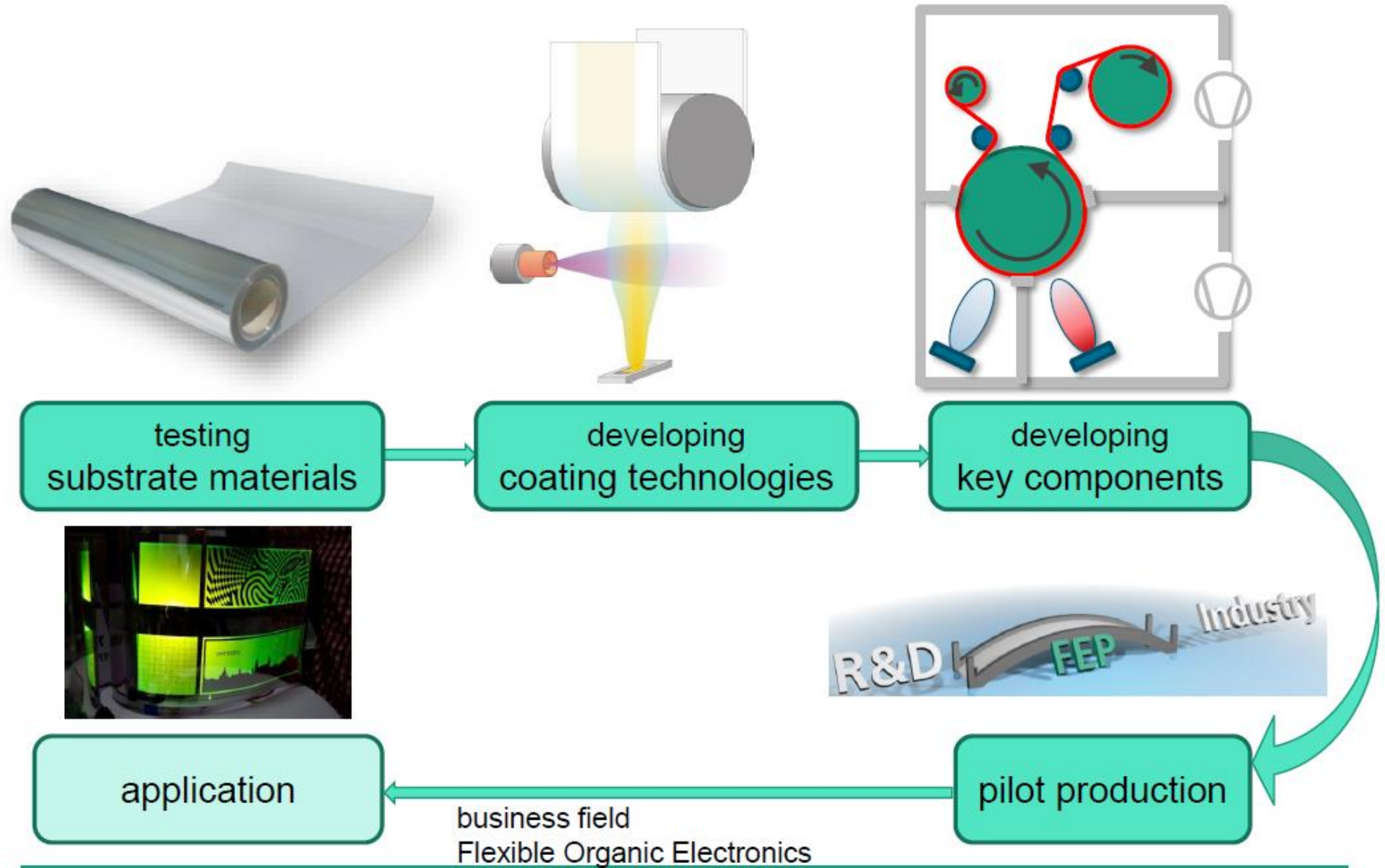
What FEP can do for various industries?

## R2R coating technologies

for flexible organic electronics



# FEP's business field based on R2R coating technologies



# FEP's key component technologies for pilot and production

1. Hollow cathode discharge Assisted  
high rate Deposition (**HAD**)
2. High rate PECVD (magPECVD, **arcPECVD**)
3. High rate sputtering for precision optics(**RM**)  
with pulsed powering & process control



# 1, Hollow cathode discharge Assisted high rate Deposition (**HAD**)

Discharge current  $\sim 200\text{A/gun}$



Extremely high density plasma

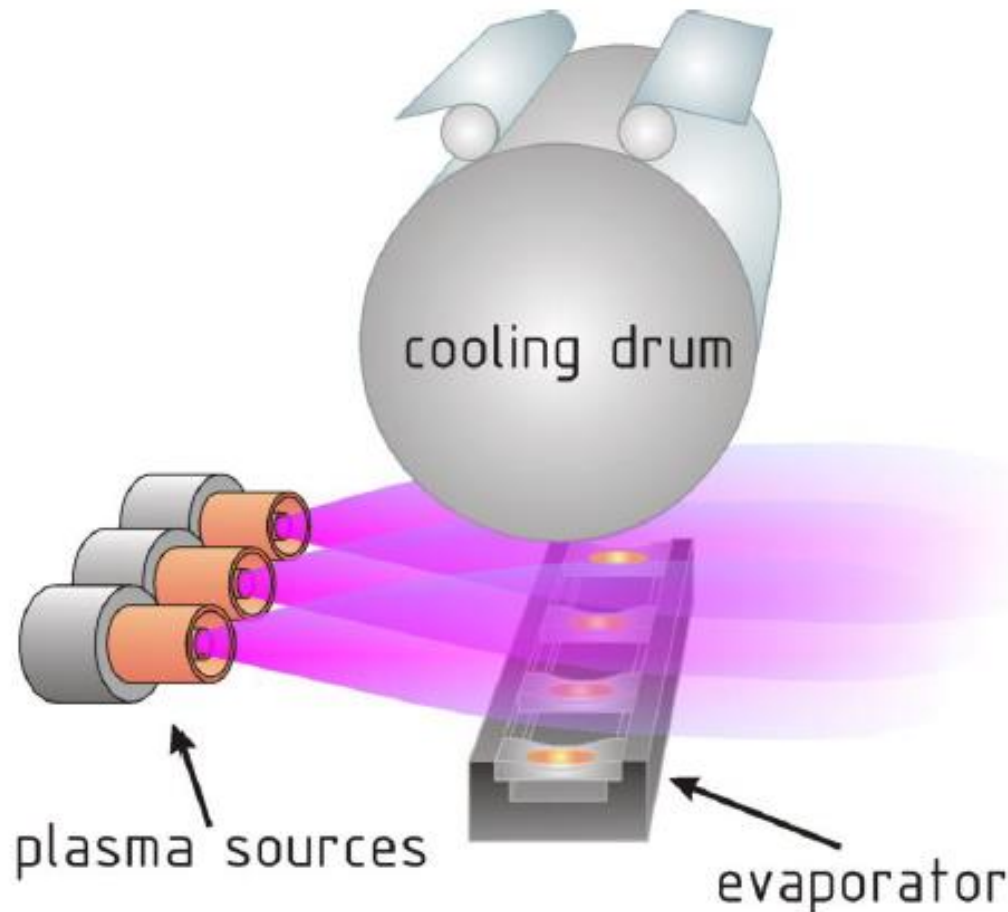


Strong ion bombardment



Dense coating with high rate

**> 2000nm.m/min**



<Similar plasma gun>

**\*UR gun in Japan**

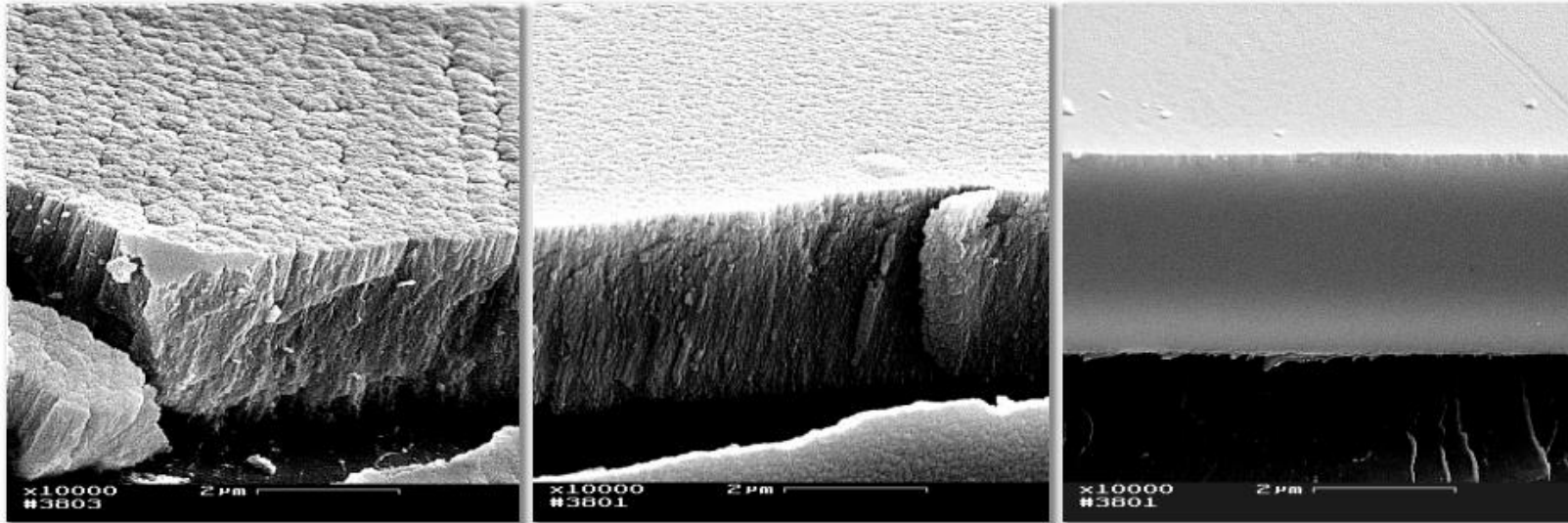
(Pressure gradient arc plasma gun)

**\*ETP source in The Netherlands**

(Cascade arc plasma gun)

# Effect of Plasma Activation

Example:  $\text{Al}_2\text{O}_3$  on PET at 100 nm/s



$\text{Al}_2\text{O}_3$  by reactive  
evaporation

Discharge current: **0 A**

Layer hardness: **3.2 GPa**

$\text{Al}_2\text{O}_3$  by reactive  
evaporation

Discharge current: **200 A**

Layer hardness: **5.0 GPa**

$\text{Al}_2\text{O}_3$  by reactive  
evaporation

Discharge current: **400 A**

Layer hardness: **6.3 GPa**



**Dense amorphous layer morphology by plasma activation**

# Linear plasma gun for large area high rate deposition



310cm

**Current application**

→ **Food packaging**  
(~20nmAlO<sub>x</sub>, 9m/s)

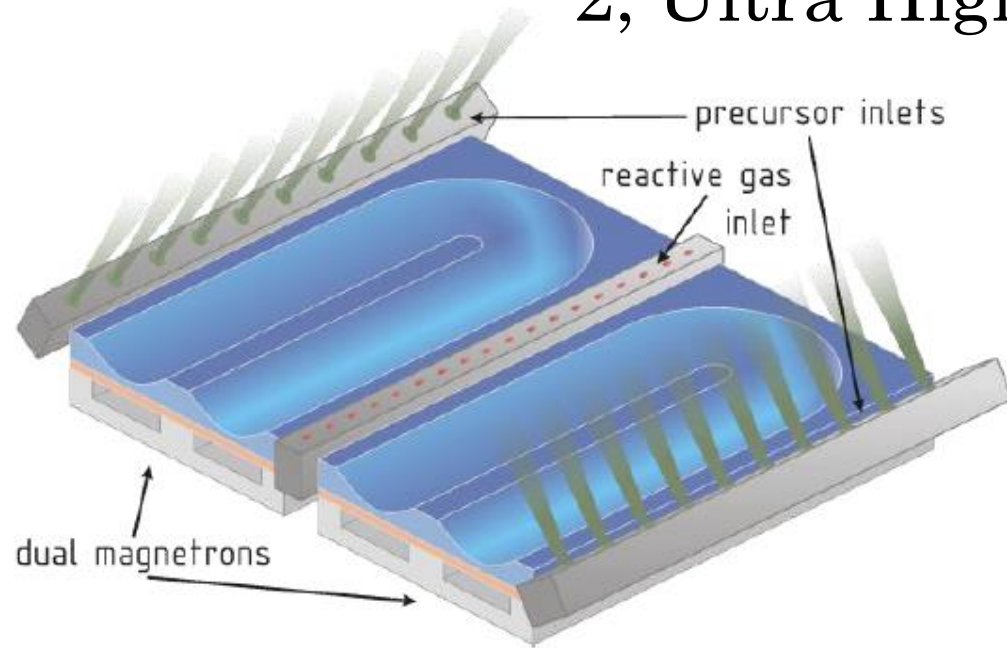
**Hardware**

→ **ready for production!**

**Application also to**

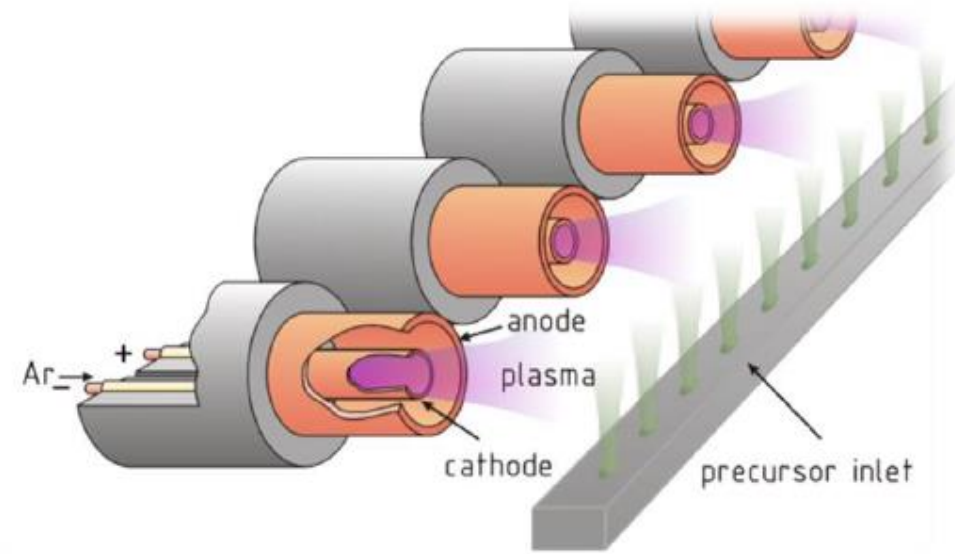
→ **arcPECVD !!**

## 2, Ultra High Rate PECVD



### Dual Magnetron PECVD

- same plasma source usable for sputtering and PECVD
- deposition rate up to 400 nm·m/min

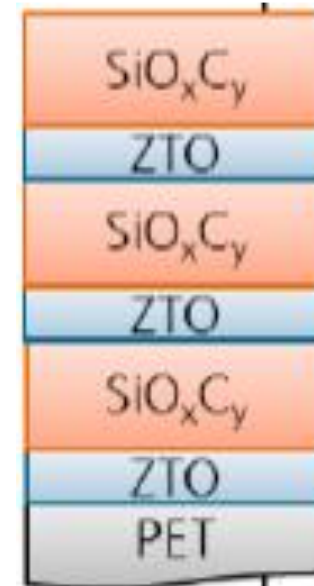
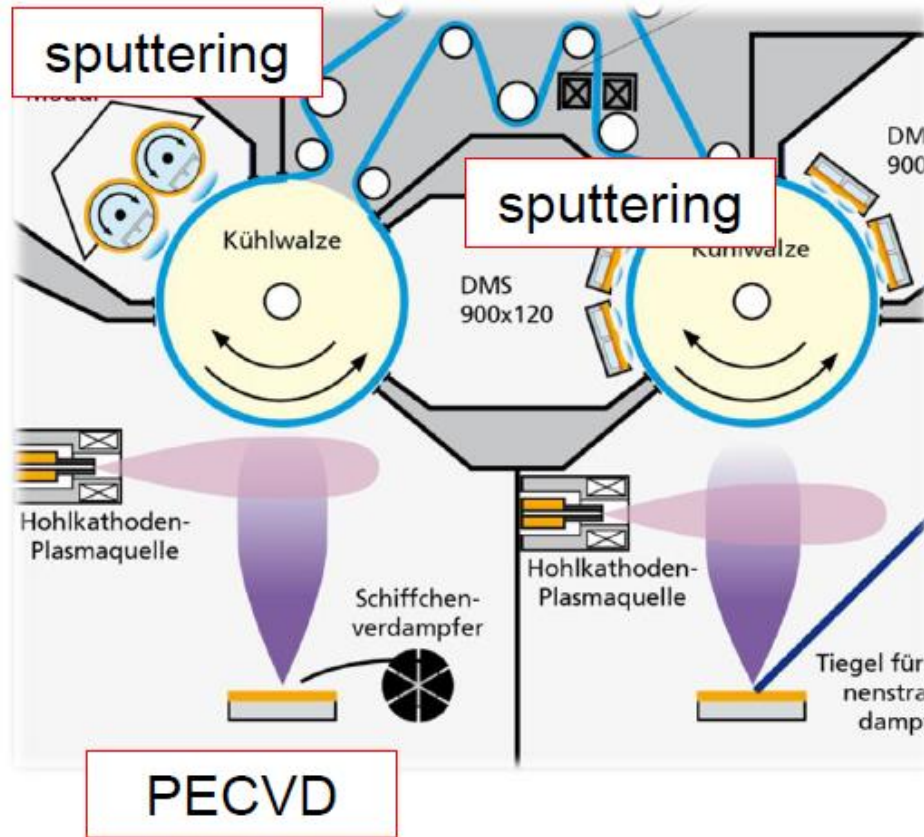


### Hollow Cathode arc-PECVD

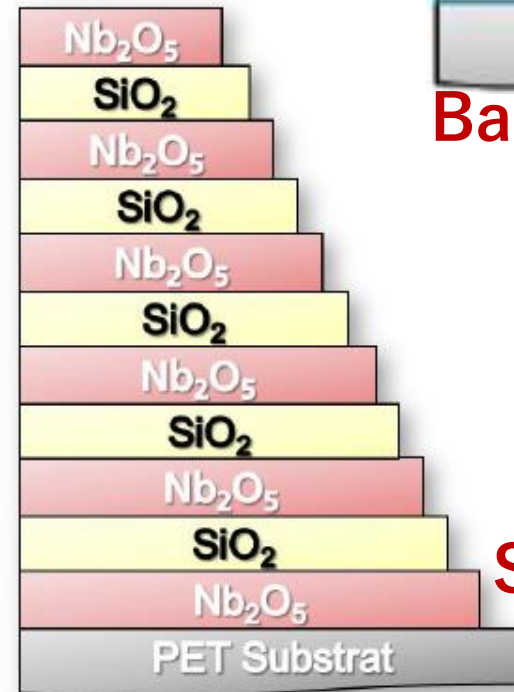
- high-density plasma
- deposition rate up to 2500 nm·m/min

- SiO<sub>2</sub> and SiO<sub>x</sub>C<sub>y</sub>H<sub>z</sub> plasma-polymer layers using HMDSO
- process pressure < 1 Pa
- inline compatible to reactive sputtering

# Application of magPECVD and arcPECVD



**Barrier film**

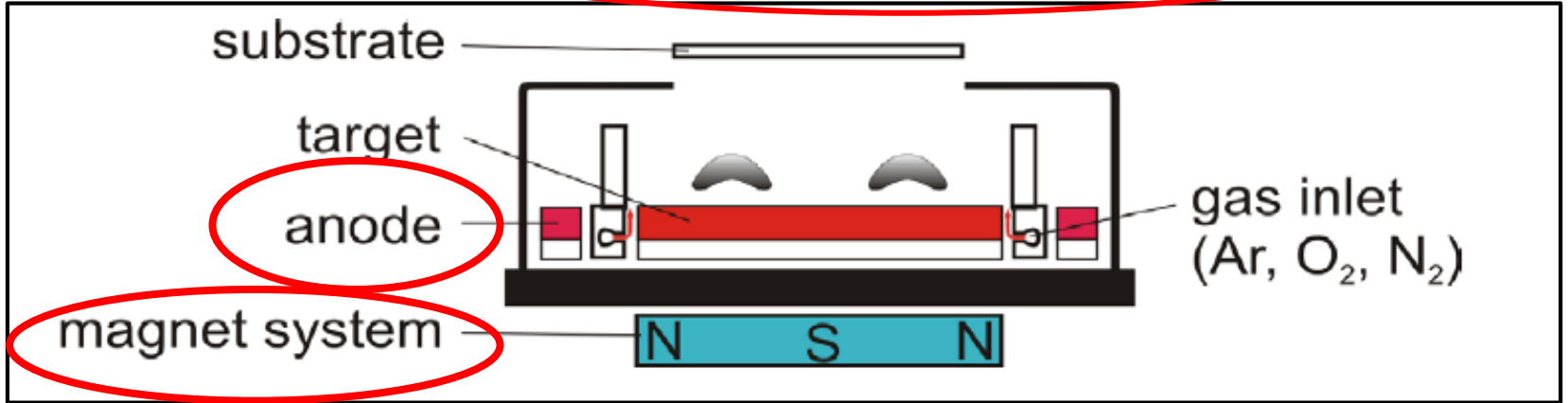


**Solar control**

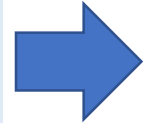
- inline compatible processes
- high deposition rate with PECVD possible up to 500 nm·m/min for SiO<sub>2</sub>  
up to 3000 nm·m/min for Plasmapolymers

### 3, FEP's RM sputtering technology with pulsed powering & process control

↔ DMS  
C-mag



- 1. High rate
- 2. Excellent uniformity <math><+-0.5\%</math>
- 3. Long term stability
- 4. **Low temp. & Low damage**

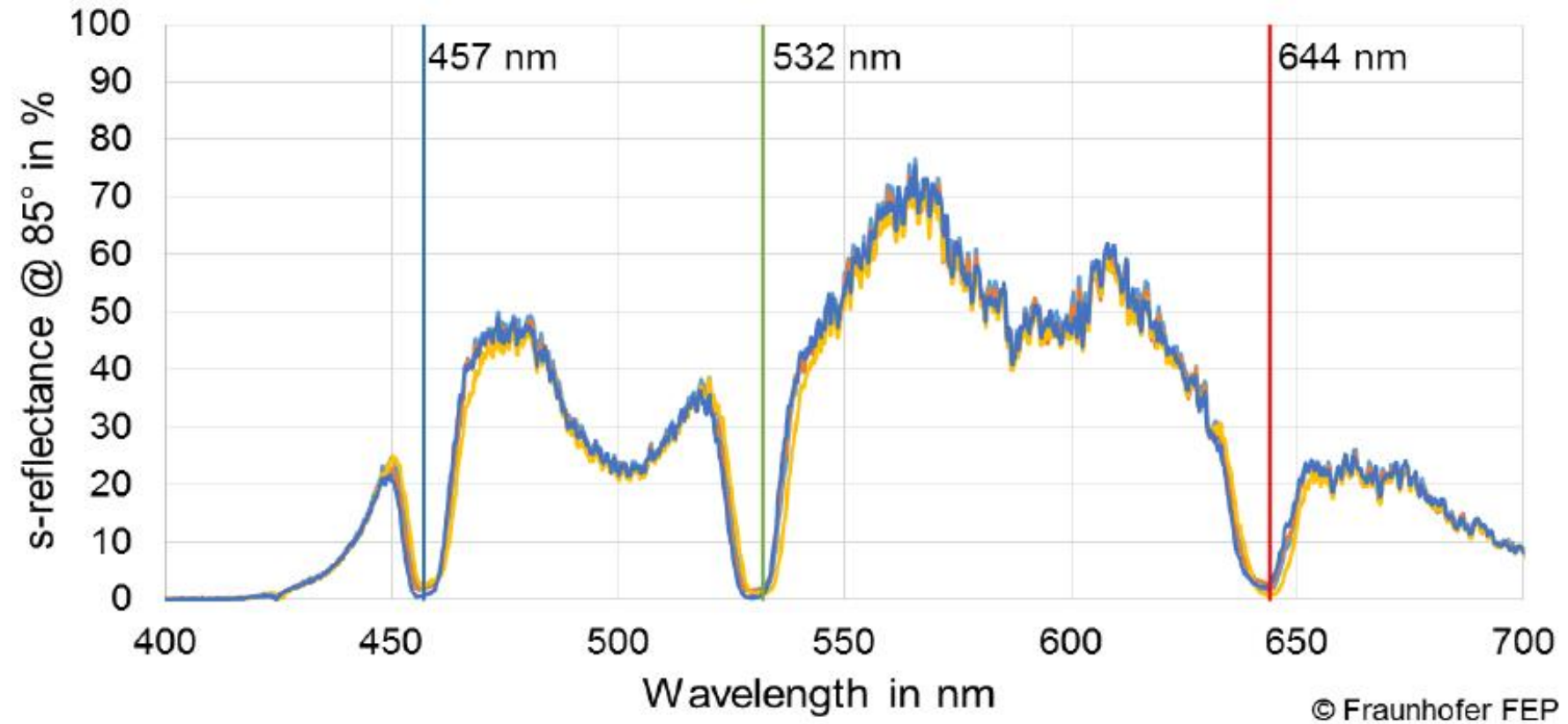


- 1. Large area precision optics
- 2. Thin film encapsulation for OLED
- 3. Inorganic barrier film
- 4. **Plastic substrate**

# Anti reflective (AR) coating for back-light of holographic display



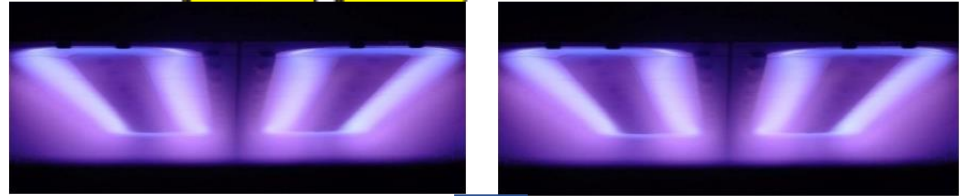
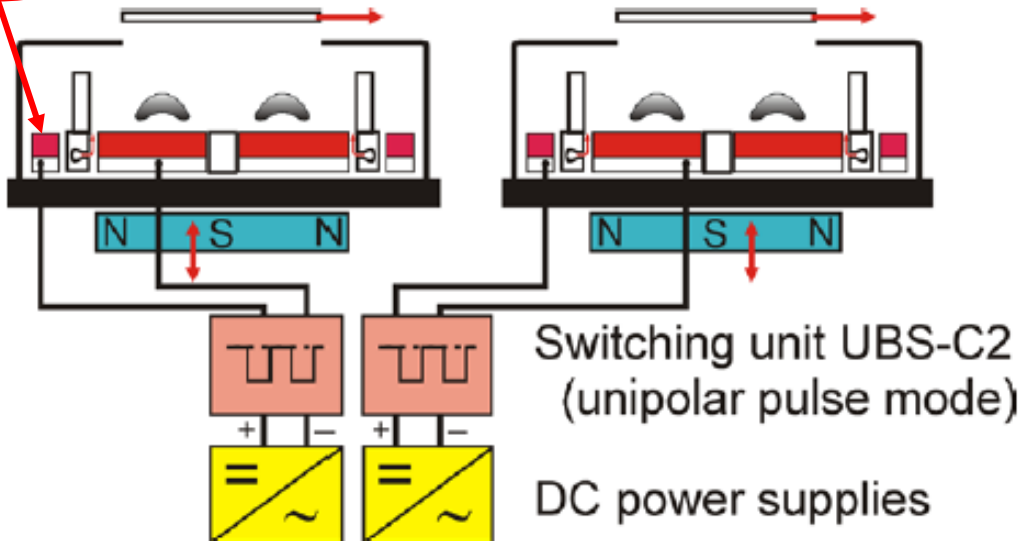
RGB AR coating:  
Measurement of s-Reflectance @ 85° angle of incidence,  
center + edges of 20" substrate (300x400 mm)



# Pulsed powering in RM

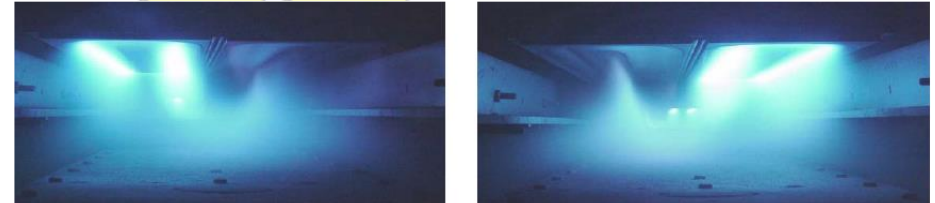
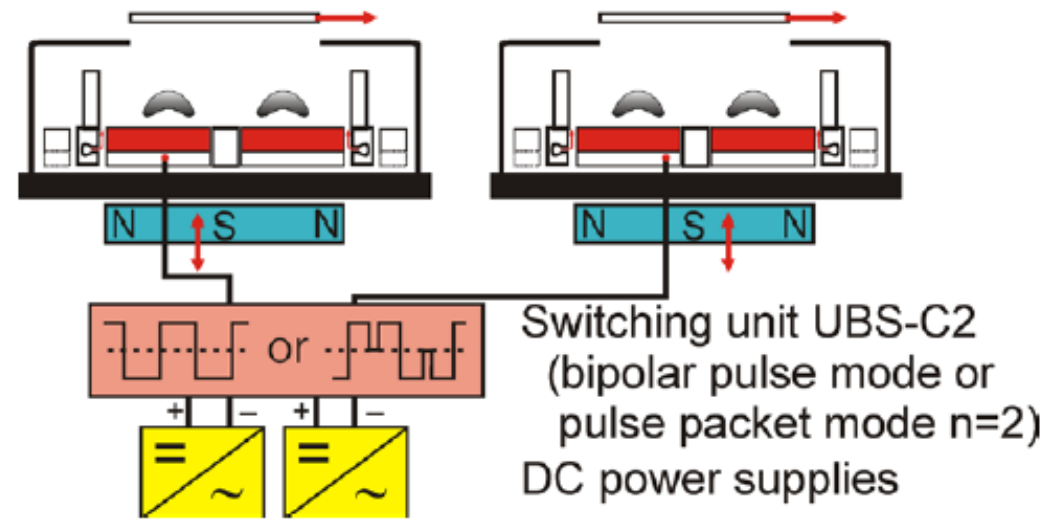
Hidden Anode

## Unipolar mode



Low temperature  
Low damage

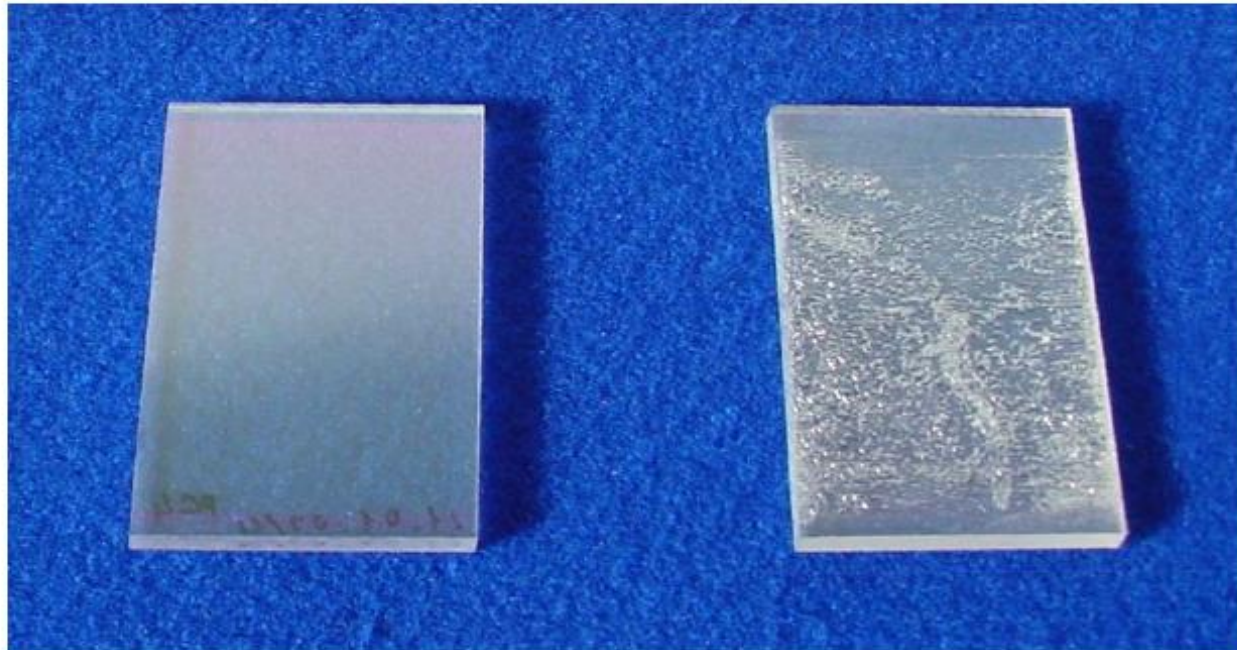
## Bipolar mode



High ion bombardment,  
High thermal load



# Energetic substrate bombardment in unipolar and bipolar pulse mode



Unipolar

( $T_{\max} = 143 \text{ }^{\circ}\text{C}$ )

- Better suited for coating on temperature sensitive substrates

Bipolar

( $T_{\max} = 204 \text{ }^{\circ}\text{C}$ )

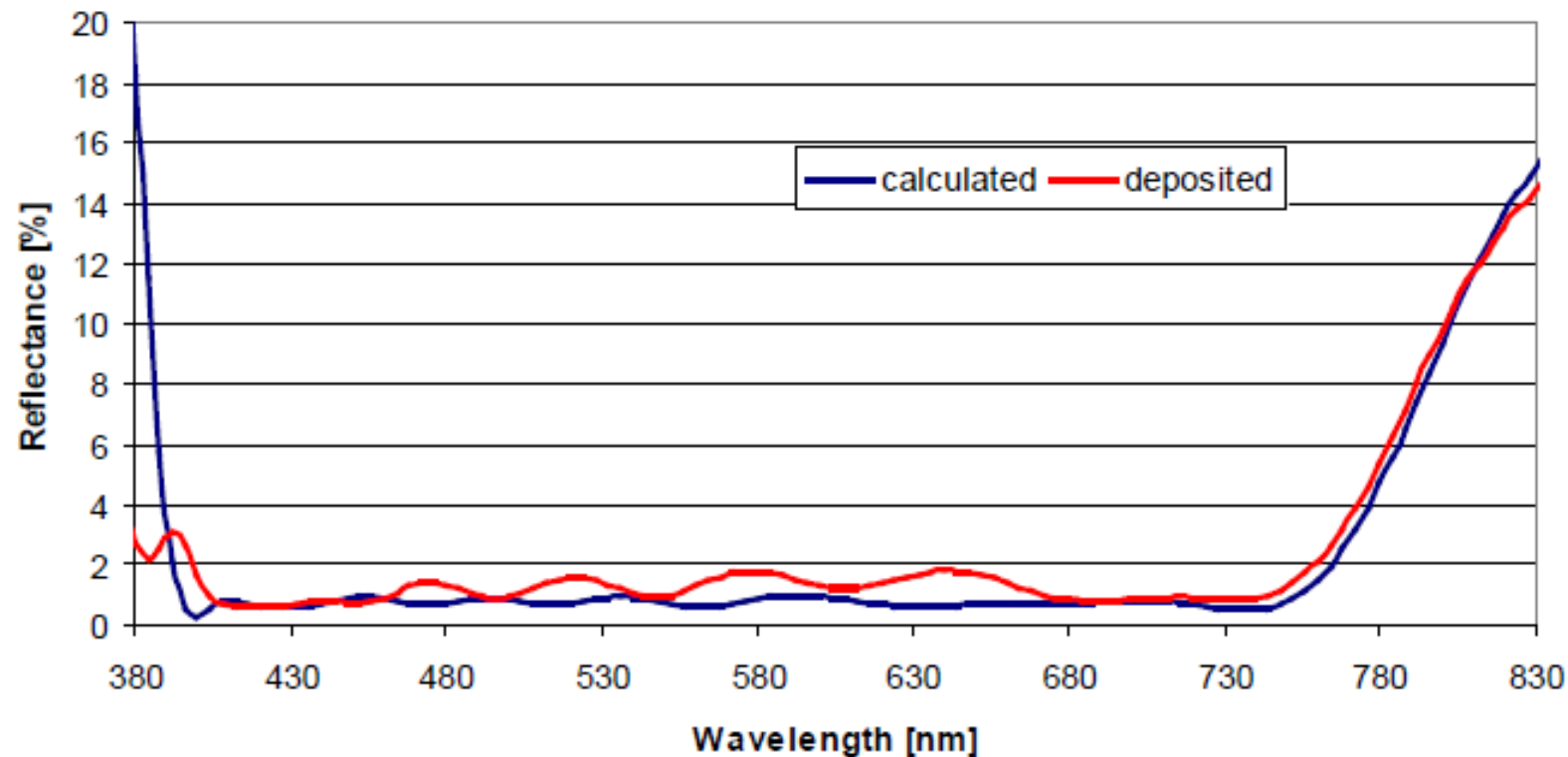
- Better suited for Deposition of very dense (stable) films

- Substrate: polycarbonate (PC)
- Layer material:  $\text{TiO}_2$
- Layer thickness: 500 nm

# Broadband antireflection gradient coatings for plastic substrates (Design: AR hard<sup>®</sup>)

Collaboration with IOF, Jena

Design: Dr. U. Schulz

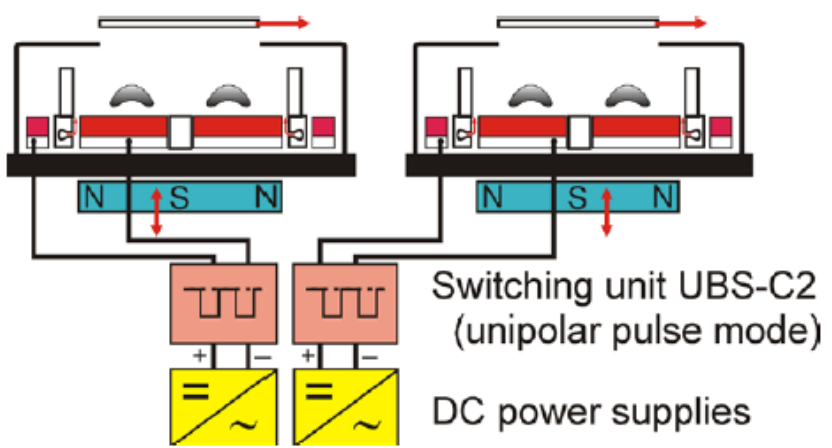


Reflectance spectrum of an AR-hard coating system with

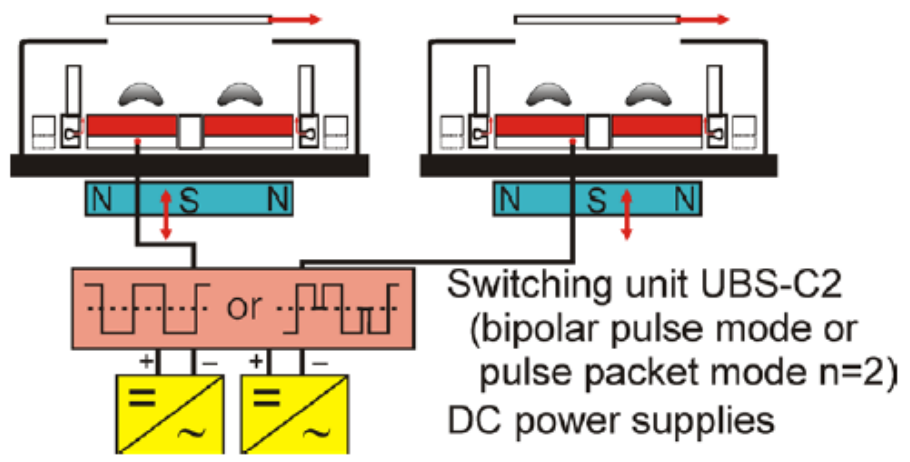
- 17 layers (SiO<sub>2</sub>/Si<sub>3</sub>N<sub>4</sub>) applied on both sides of a PC-substrate
- total thickness 1.8 μm

# New approach to adjust film property in RM

## Unipolar mode



## Bipolar mode



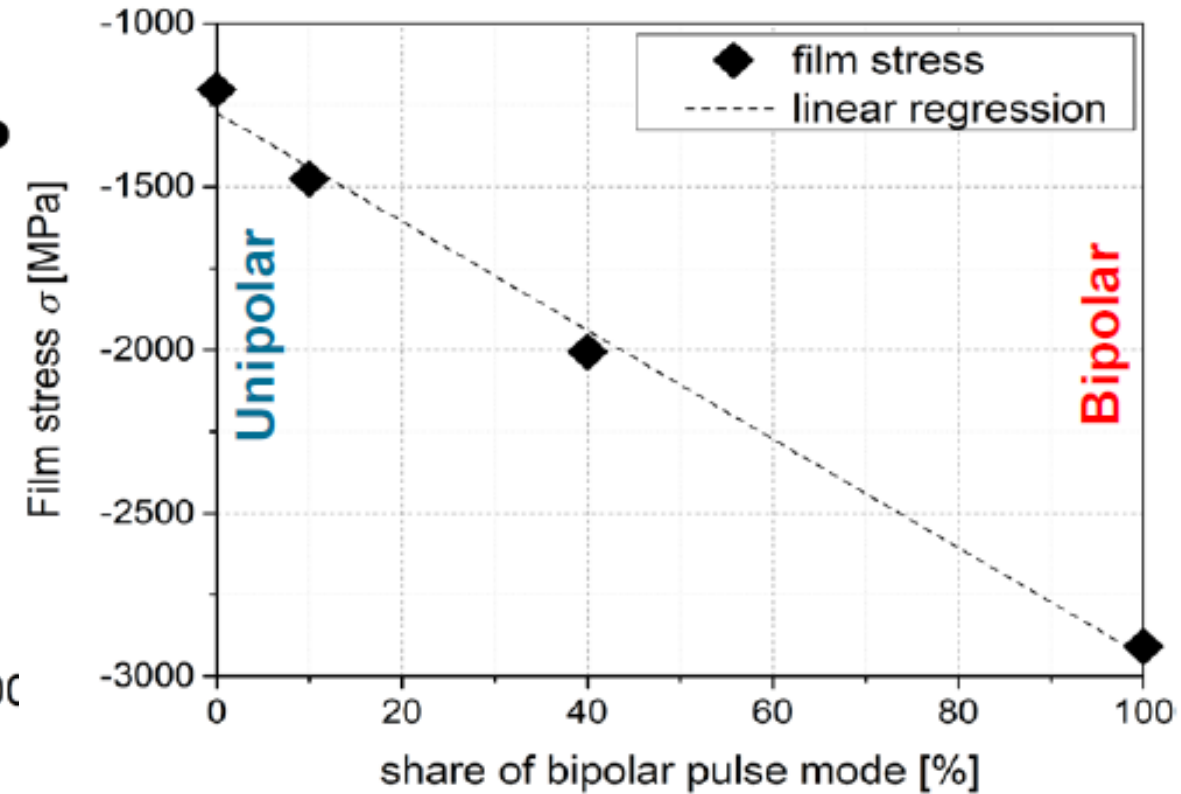
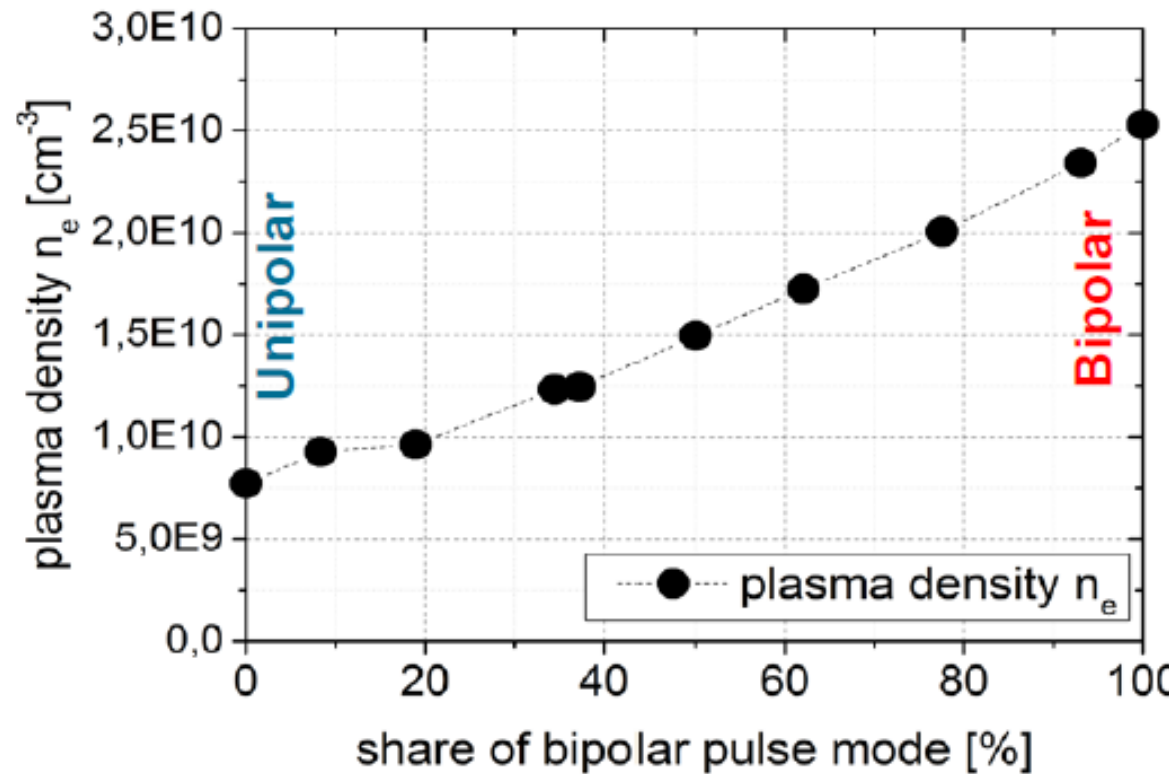
Switching At 1kHz



Unipolar pulse mode	U/b hybrid pulse mode	Bipolar pulse mode
moderate	intermediate	strong
bombardment of the growing thin film by high energy particles		

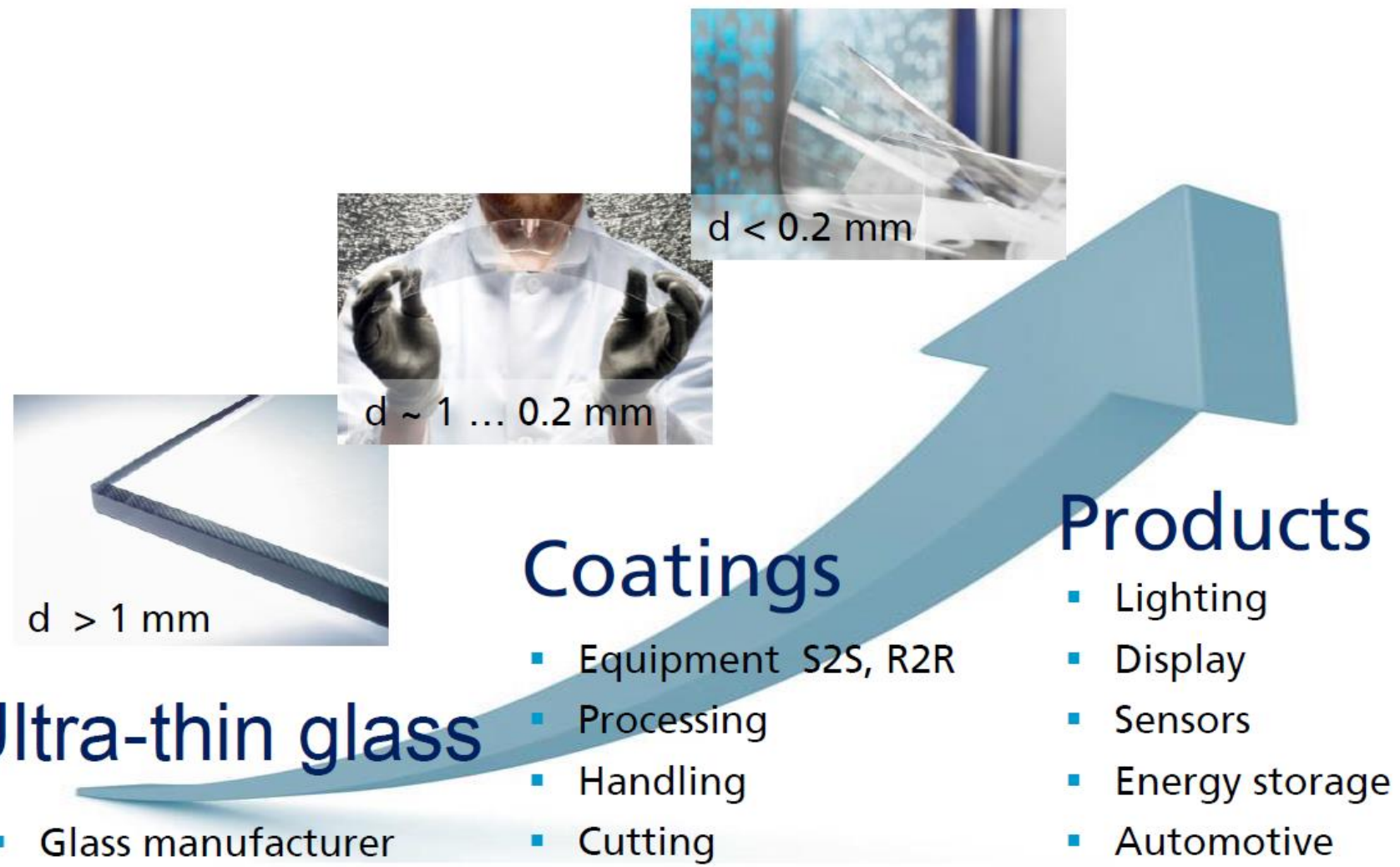
# Hybrid Pulse Mode

**Plasma density & film quality control independent from the input power !!**



# Coatings on flexible ultra thin glass

# Progress in ultra-thin glass (UTG) product development



Corning, Schott, NEG, AGC, etc.

$\sim 30 \mu \text{m t}$

# VISION | FLEXIBLE GLASS

[www.fraunhofer.fep.de](http://www.fraunhofer.fep.de)

**WORKSHOP**

**»COATING ON FLEXIBLE GLASS«**

**APRIL 4-5, 2017**

**DRESDEN, GERMANY**



## Example – AR Coatings on ultra-thin flexible Glass

*Anti-reflective coating on 50  $\mu\text{m}$  flexible glass*



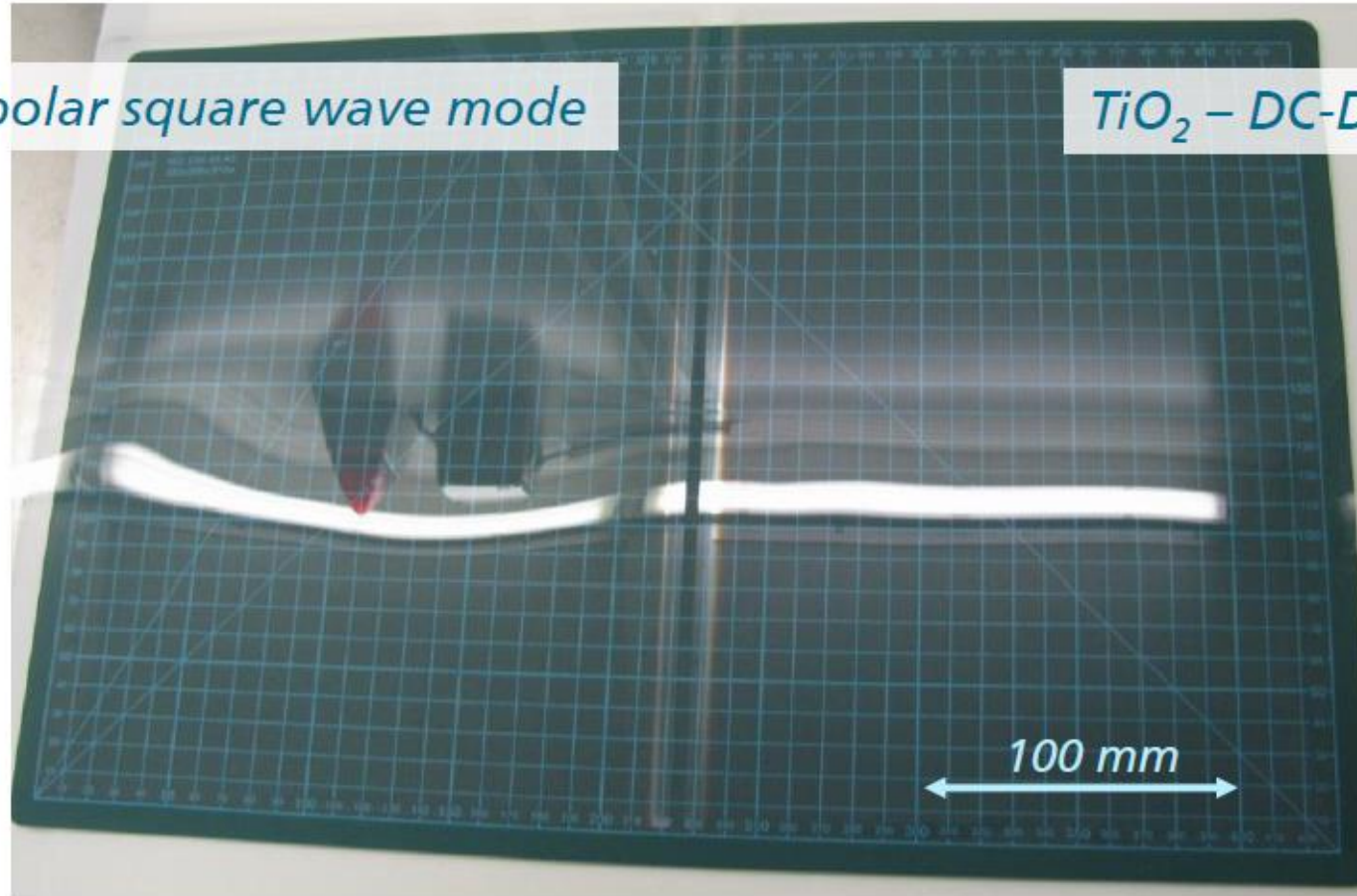


## Example – AR Coatings on ultra-thin flexible Glass

*Only one side is coated!!!*

*TiO<sub>2</sub> – bipolar square wave mode*

*TiO<sub>2</sub> – DC-DC mode*



*film stress layer stack: -175 MPa*

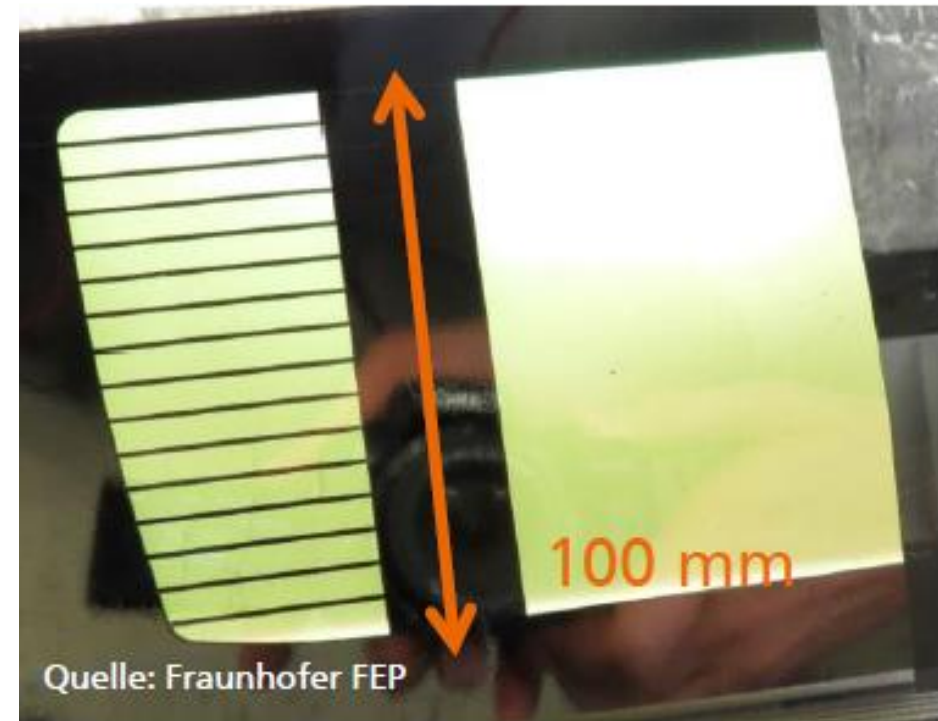
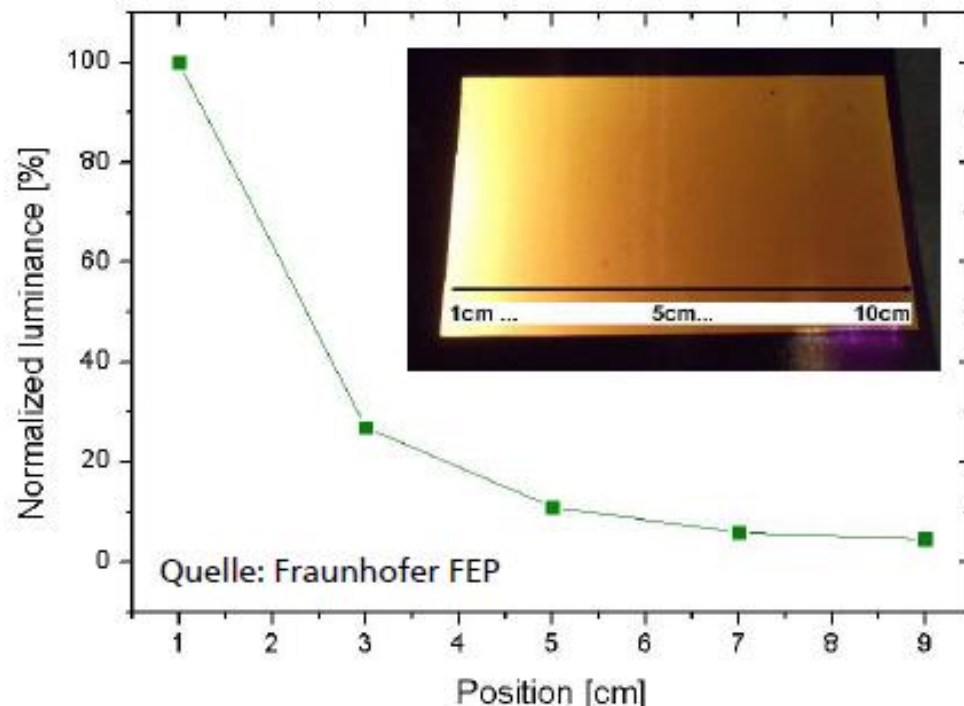
*-75 MPa*

# TCO electrode for flexible OLED lighting

POLO film (PET)+ITO(35Ω/sq)  
 → 90% reduction in brightness

Ultra thin glass+ITO(12Ω/sq)  
 → Uniform brightness in 10cm<sup>2</sup>

*OLED on ITO POLO barrier web*



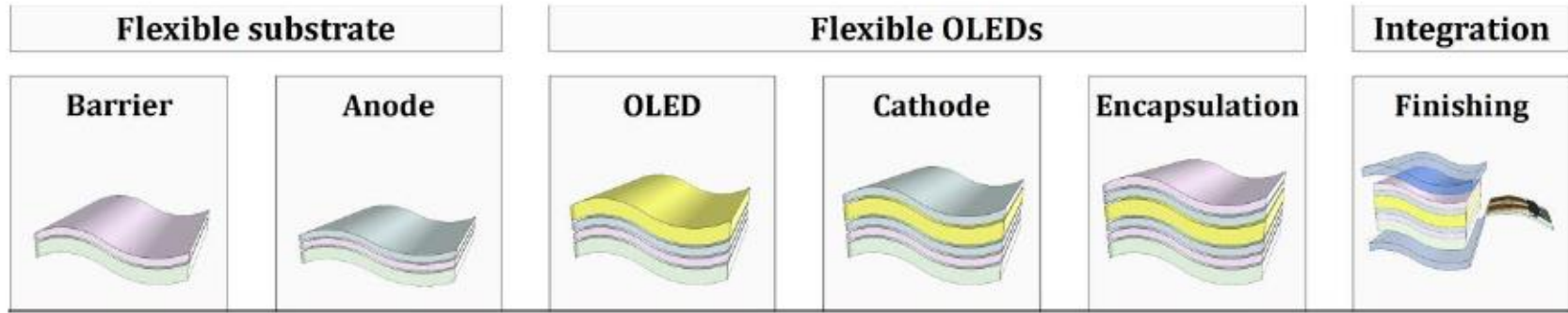
## Vacuum R2R coater for flexible ultra thin glass

- \*Substrate width: **330mm**
- \*Heating: **< 350°C**
- \*Thickness : **>50  $\mu\text{m}$**
  
- \*4 coating zones
- \*Dual anode sputtering
- \*Front-side touchless



# Flexible OLED lighting

# Portfolio of the Division Flexible Organic Electronics



## Flexible Organic Electronics

- S2S sputtering for electrode (up to 370x470mm<sup>2</sup>)
- S2S layer deposition via printing, slot die coating, spin-coating
- S2S OLED deposition by evaporation (up to 200x200mm<sup>2</sup>)

- R2R barrier web
- R2R magnetron sputtering for electrode deposition
- R2R structuring via printing
- R2R-OLED deposition
- R2R lamination



- Laser ablation
- Laser cutting
- Laser structuring

# OVERVIEW PROCESS FLOW IN R2R R&D LINE

R2R inspection system



R2R vacuum coater

R2R printing and lamination unit (N<sub>2</sub>)

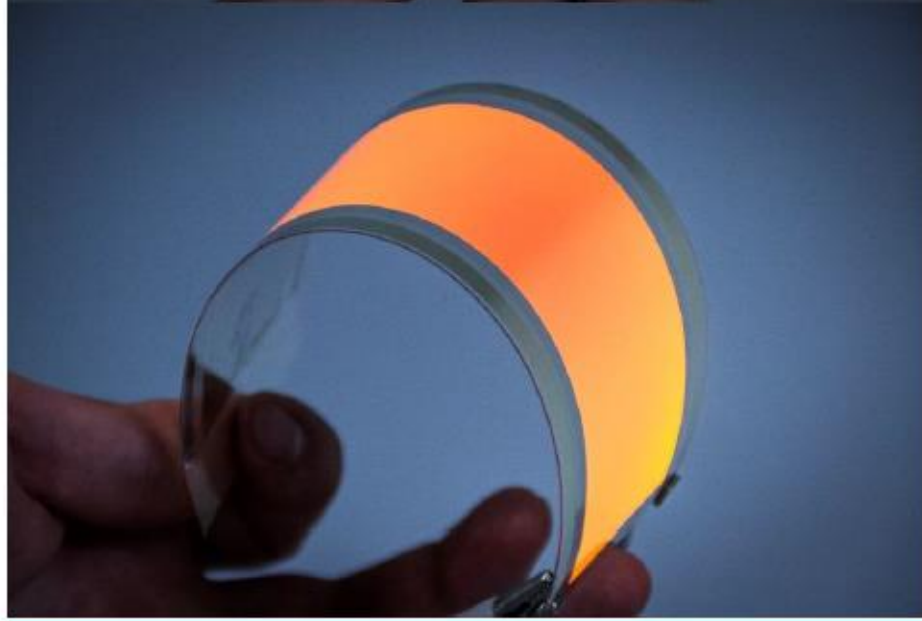
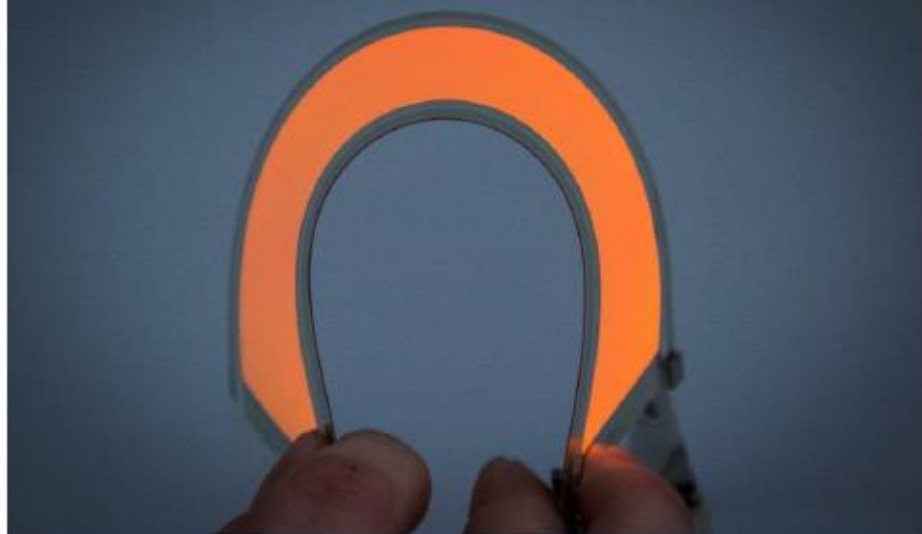


- Typically **300 mm** web width
  - metal strips: thickness up to 500  $\mu\text{m}$
  - **polymer webs** : thickness 50 to 500  $\mu\text{m}$
  - **flexible glass** : thickness 50 and 100  $\mu\text{m}$  preferably (“pure” or laminated on PET)

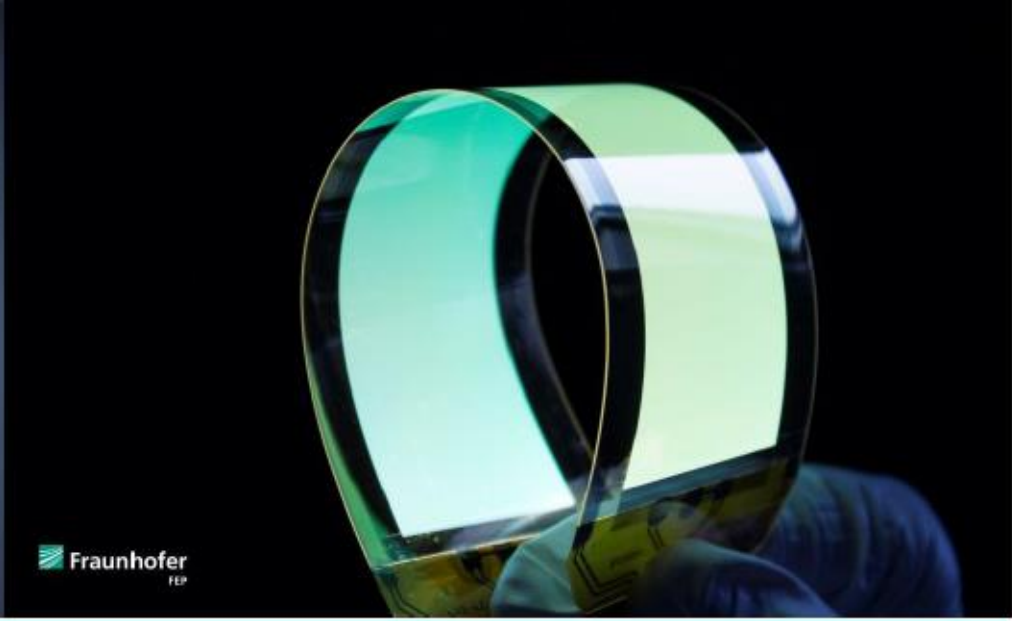
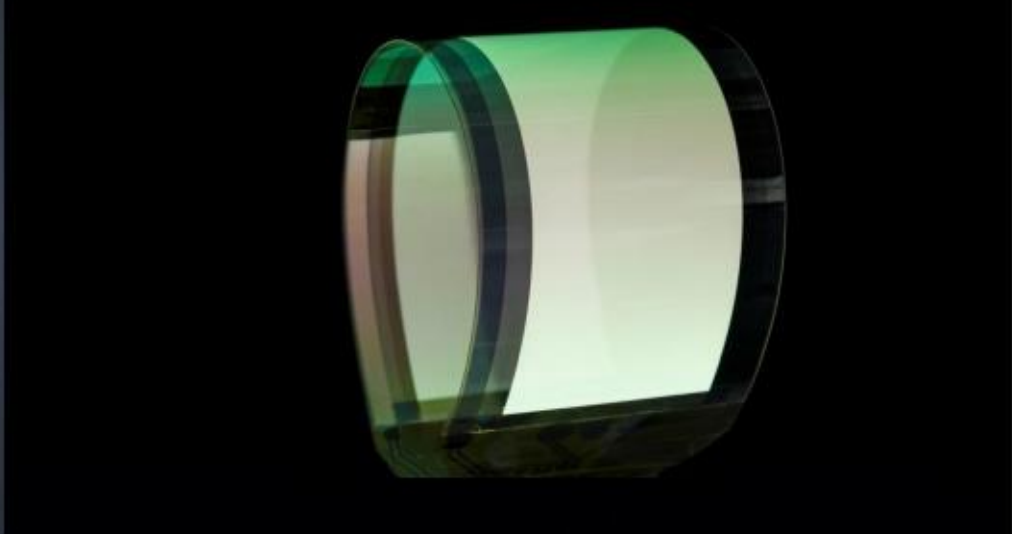


# OLED on plastic foil @ Fraunhofer FEP

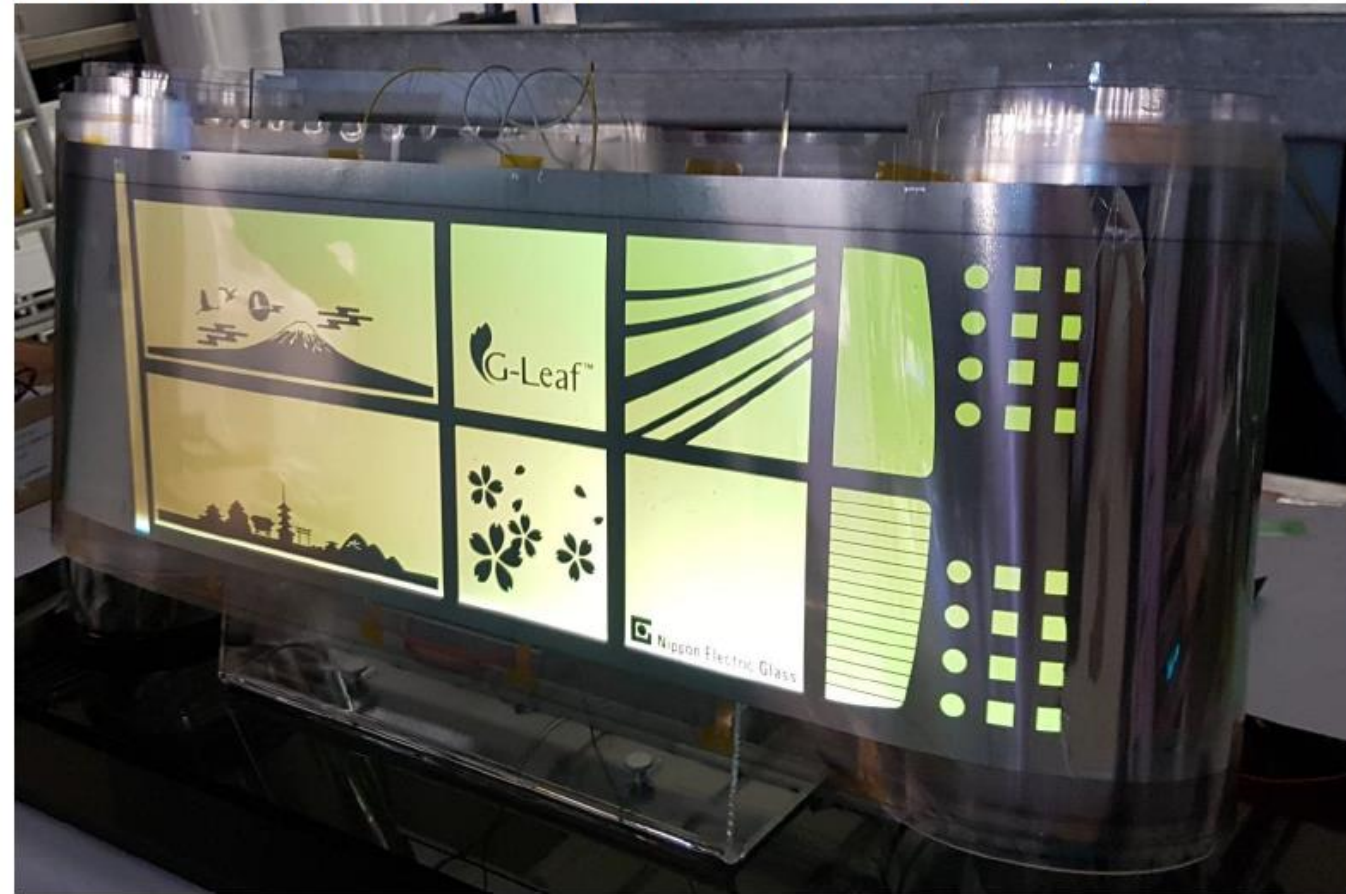
Bottom Emitting OLED



Semi-transparent OLED



# R2R OLED ON ULTRA THIN GLASS ENCAPSULATED WITH ULTRA THIN GLASS (50 μm)



Demonstration of 25 x 10 cm<sup>2</sup> OLED devices without dark spot growth!  
Challenge: Development of proper cutting technology



# Current challenges in flexible OLED with plastic barrier film

## How to stop black spot formation!!

Factors to affect on OLED life :

WVTR + \* Residual water and drying method

- \* Particles
- \* Handling and mechanical strength
- \* Residual stress, adhesion
- \* Residual organic solvent & reaction
- \* Device structure & optical property

Ex. : Effect of vacuum drying of barrier film on OLED life



80°C、1 week

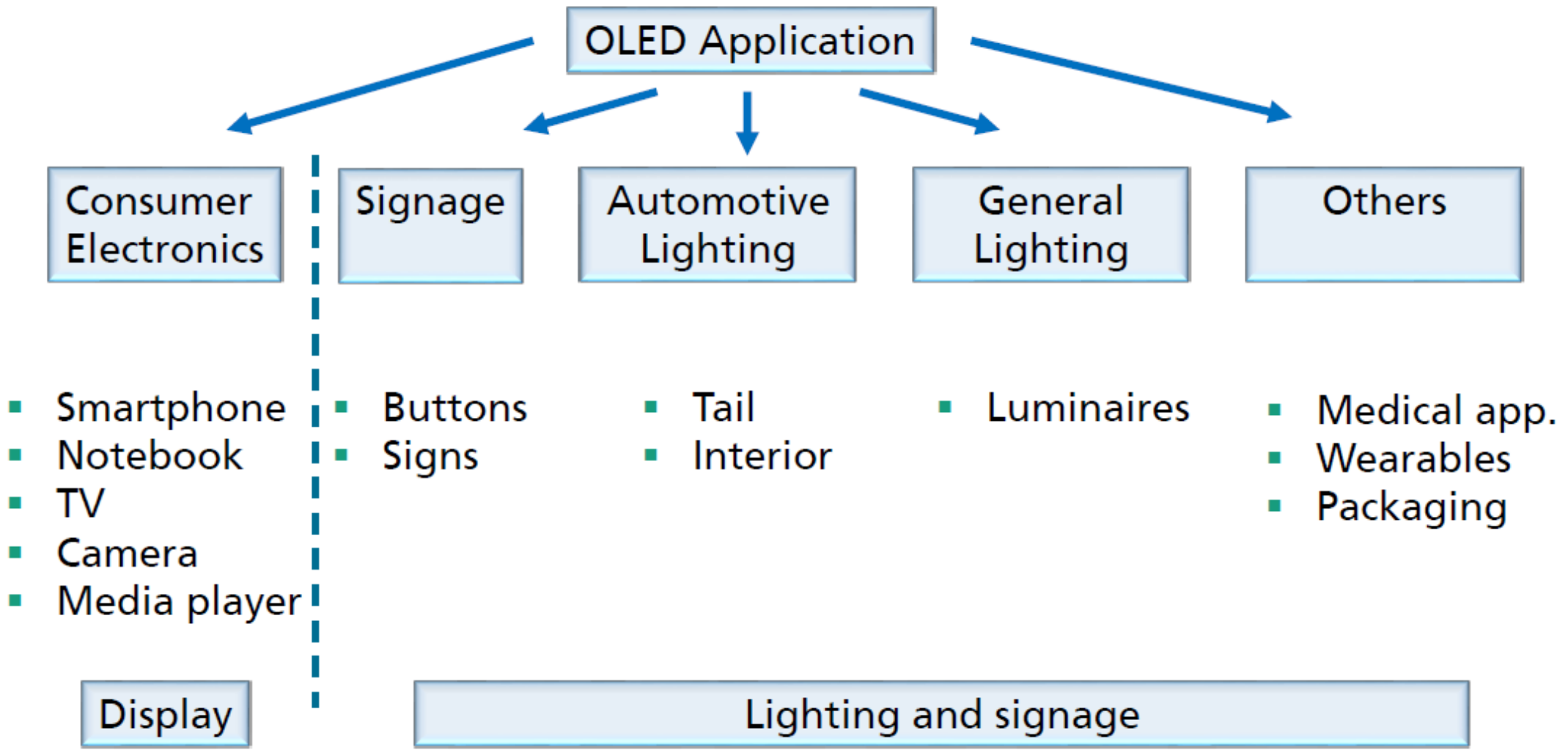


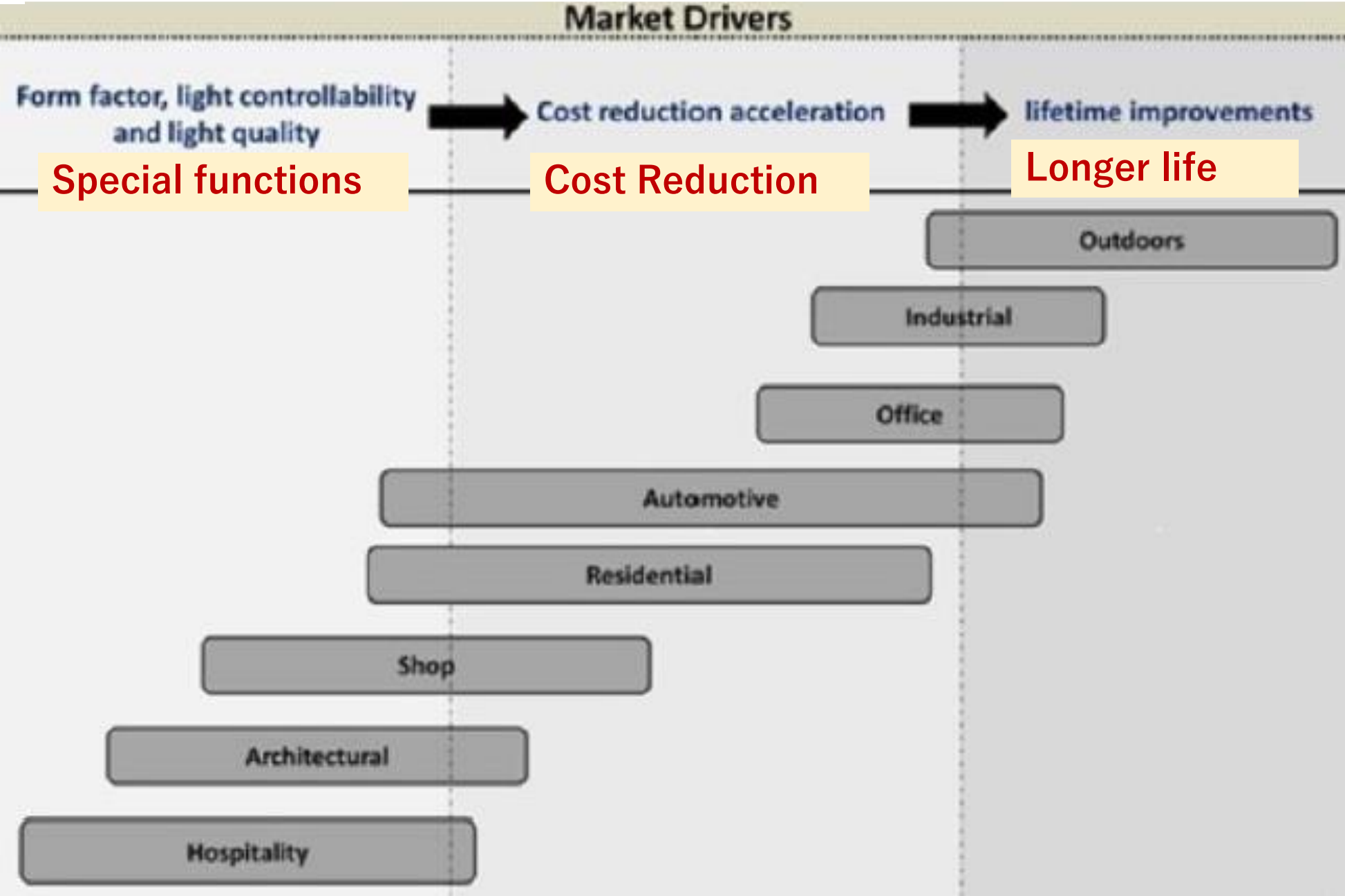
80°C、160hrs



80°C、100min

# OLED APPLICATIONS





# OLED Luminaires

**Necessity of killer application!!**

Innovation vs. Preis

Current status:

~~Standard-OLED Module → Luminaire~~

Goal:

„shapeable“-OLED = luminaire

(Exceptional: Hybrid-Luminaire LED/OLED)



Quelle: Tom Dixon



Quelle: Marcus Tremont

Quelle: Zumtobel (Fotomontage)

# Application scenario automobile

Short-term:

OLED Integration in back lights

- 3-dimensional distribution of rigid glass OLED devices or flexible OLED-module in lighting bodies (complemented with LED)



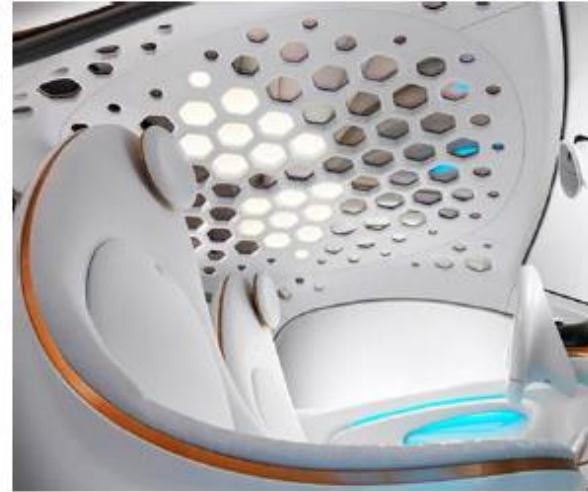
Quellen: Hella; Bimmerpost

OLED backlight in Audi TT: <http://www.audi.de/de/brand/de/neuwagen/tt/tt-rs-coupe-tt-rs-roadster.html#>

# Application Automobile

Long term:  
Interior lighting

- Large area transparent OLED lighting in the roofs
- e.g. Smart Forvision Study with BASF



A dream for designers:  
Lighting in the car body

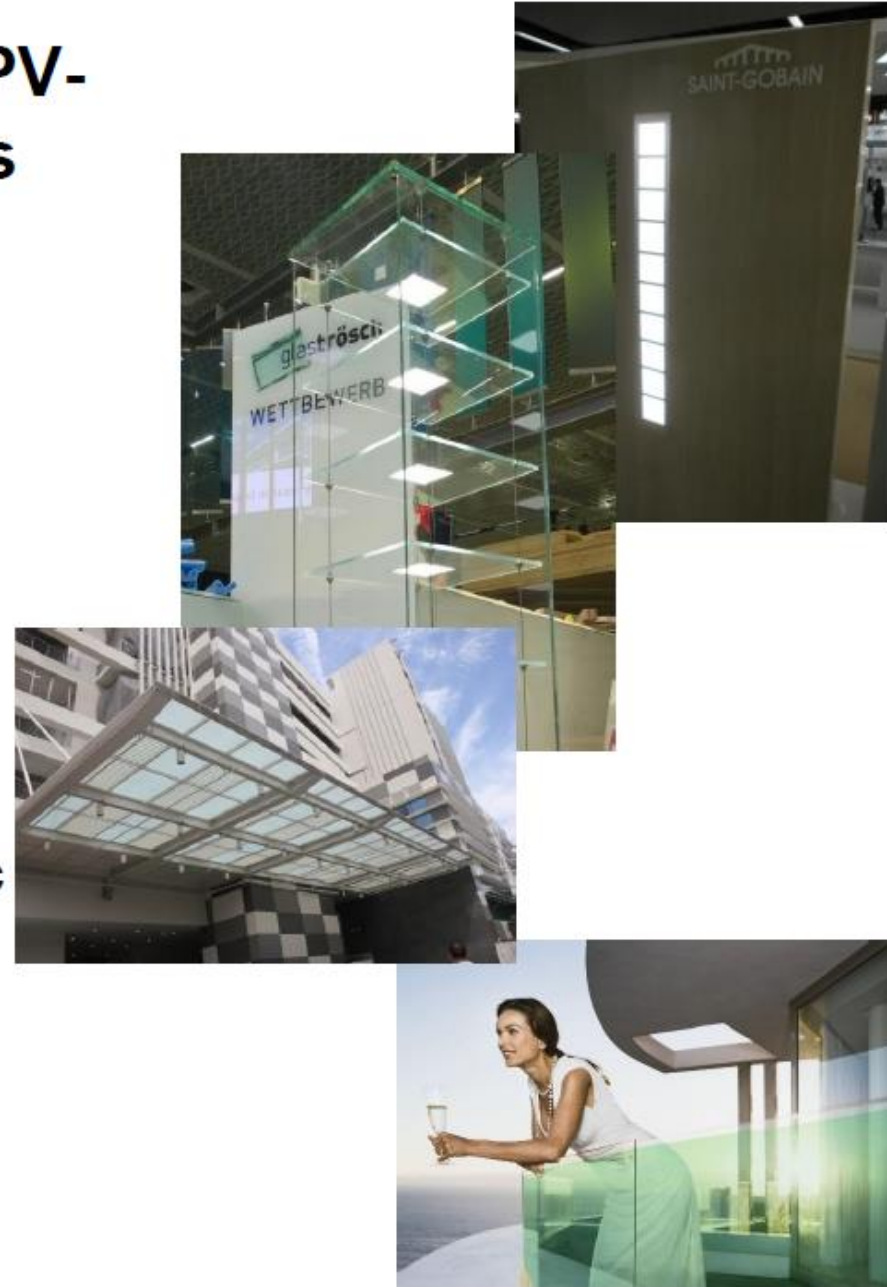
- Lighting contours for recognition at night
- Removing of classical headlights
- e.g. Study from Audi



**For visual communication with humans !!**

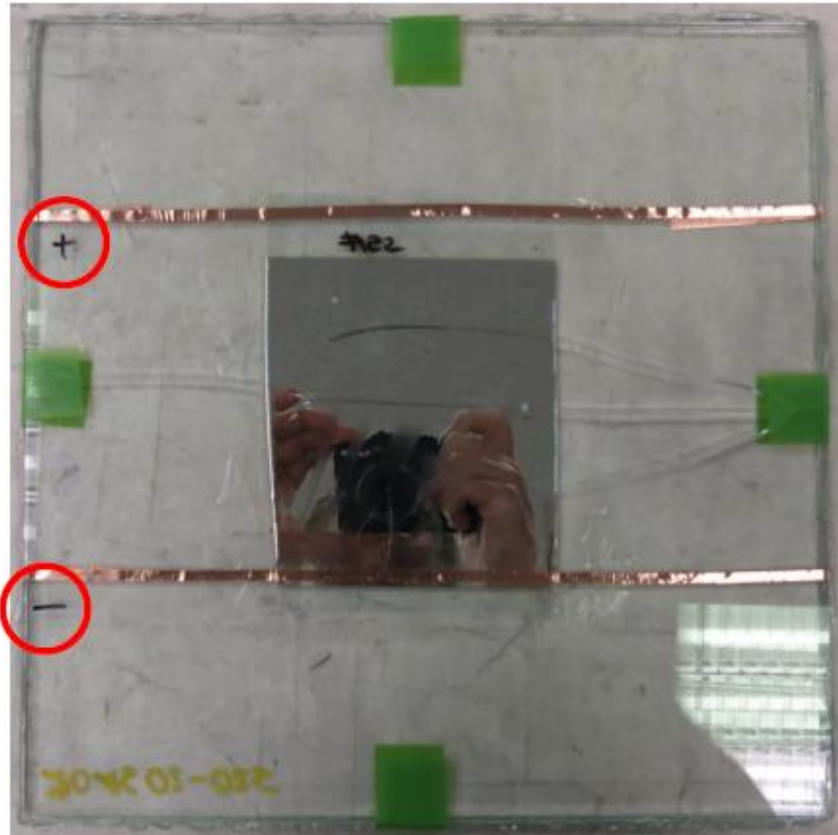
# Technological trends: OLED/OPV- Integration into Glass laminates

- OLED – first demonstrator
  - Integration in room separator (St. Gobain with LG Chem on Light&Building 2014)
  - Integration opaque modules (rigid glass) in a shelf (Glas Trösch with LG Chem on Light&Building 2014)
- Building integration of organic photovoltaic (BIOPV)
  - Heliatek in Singapur (Mai 2015): HeliaFilm® into glass roof (15% and 30 % transparency) in different color.

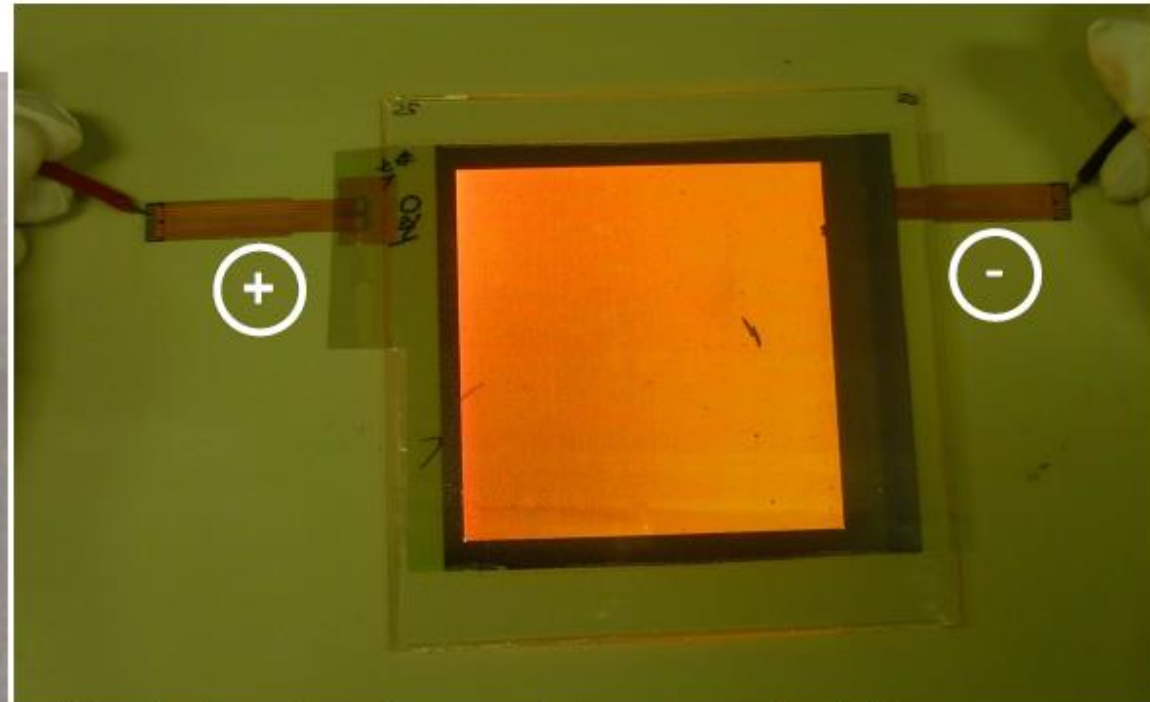


# Flexible OLED on plastic barrier film in glass laminates

300x300 mm Glasscheiben



OLED on plastic barrier film in glass-glass after autoclave process < 100 °C. Electrical connection using copper tape.

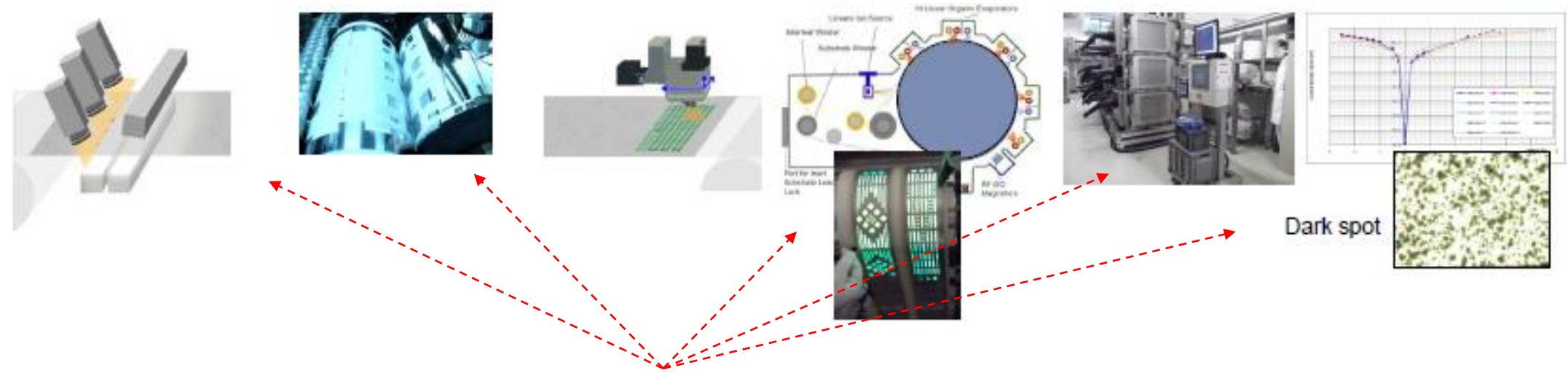
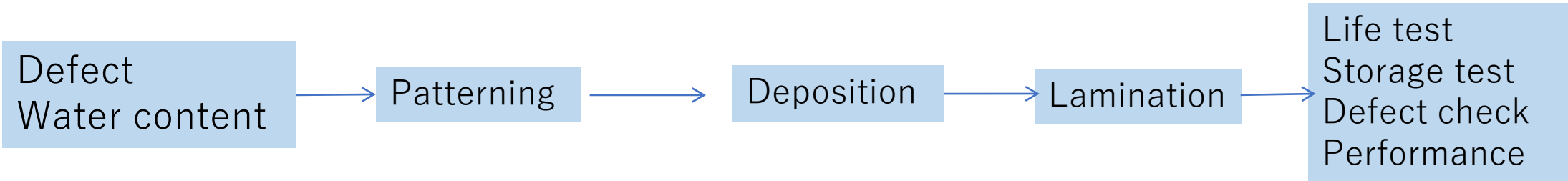


„Hot“ lamination at Fraunhofer FEP at 130°C, pressure 5 bar. Electrical connection by ACF bonding of polyimide flex cable.



# Collaboration with Japanese companies

## Evaluation of barrier films using FEP's OLED pilot line



Japanese barrier film manufacturers

## Other collaborations with Japanese companies

1. Test coating of FEP's barrier layers on the customer's substrate  
*ex. ZnSnOx by sputtering*
2. Test coatings to evaluate FEP's key component  
*ex. magPECVD, HAD, RM*
3. Introduction of key component  
*ex. RM with process control & pulse power supply, magPECVD, HAD*
4. Development of new products using FEP facilities

## Summary

\*FEP covers from coating to OLED device manufacturing

- Material and layer stack development

- Process & hardware development

- Evaluation of customers products

- Device development

- Technology package with hardware!!**

\*There are many available pilot or production technologies which might be useful also for **GPD participants!!**